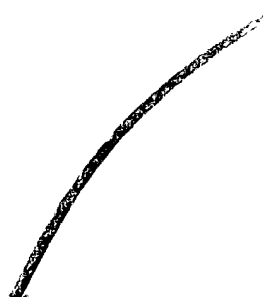


1 TANTALUM SPUTTERING TARGET AND METHOD OF MANUFACTURE

ABSTRACT OF THE DISCLOSURE

5 Described is a method for producing high purity tantalum, the high purity tantalum
so produced and sputtering targets of high purity tantalum. The method involves purifying
starting materials followed by subsequent refining into high purity tantalum.

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